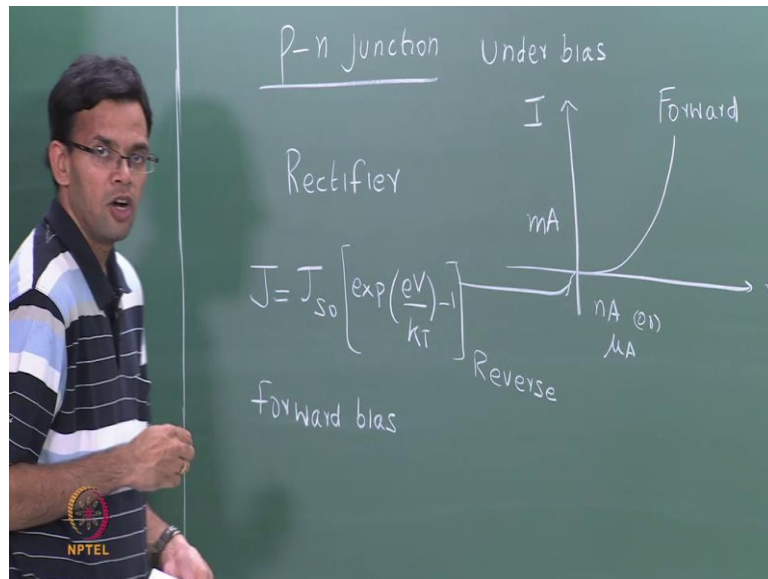


Electronic Materials, Devices and Fabrication
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Lecture - 12
PN Junction Breakdown and Heterojunctions

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Let us start with brief review of last class. Last class we look P-n junction under bias. So, we apply both power and reverse bias and look and the id characteristic, we found that P-n junction is essentially a rectifier. So, that if were to plat I verses V; this is I this is V, the first quadrant is forward bias, this 1 is reverse he found that in case of the forward bias current go to exponentially as the voltage, topical value of current mile amps. Were if have reverse bias, we have a relay small current there is of the order nano amps or micro amps that is delay constant. We also wrote down the expiration for the current, in the case of the of p-n junction. So, the expression in is J is equal to some constant js not which is your reverse saturation current times exponential ev over kT minus 1. So, this is in the case forward bias js not in the reverse saturation current.

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$$J_{s0} = n_i^2 e \left(\frac{D_h}{L_h N_D} + \frac{D_e}{L_e N_A} \right)$$

The image shows a chalkboard with the equation $J_{s0} = n_i^2 e \left(\frac{D_h}{L_h N_D} + \frac{D_e}{L_e N_A} \right)$ written in white chalk. In the bottom left corner, there is a small NPTEL logo.

So, it is equal to n_i square over $e D_h$ over $e L_h N_D$ plus D_e over $L_e N_A$. So, D_h and D_e are the diffusion coefficients for the minority carriers within the P and the n region and L_h and L_e are the diffusion length. So, today we are going to start the example, in order to calculate some of the values of the current in forward bias, also the reverse saturation current. But before we do that; I want to see how this reverse saturation current will change if you change the material.

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$$J_{s0} = n_i^2 e \left(\frac{D_h}{L_h N_D} + \frac{D_e}{L_e N_A} \right) \quad n_i^2 = N_c N_v \exp\left(-\frac{E_g}{kT}\right)$$
$$J = J_{s0} \left\{ \exp\left[\frac{eV}{kT}\right] - 1 \right\} \quad \frac{eV}{kT} \gg 1$$
$$J = \left(\frac{eD_h}{L_h N_D} + \frac{eD_e}{L_e N_A} \right) N_c N_v \exp\left[\frac{e(V - V_g)}{kT}\right] \quad V_g = E_g/e$$

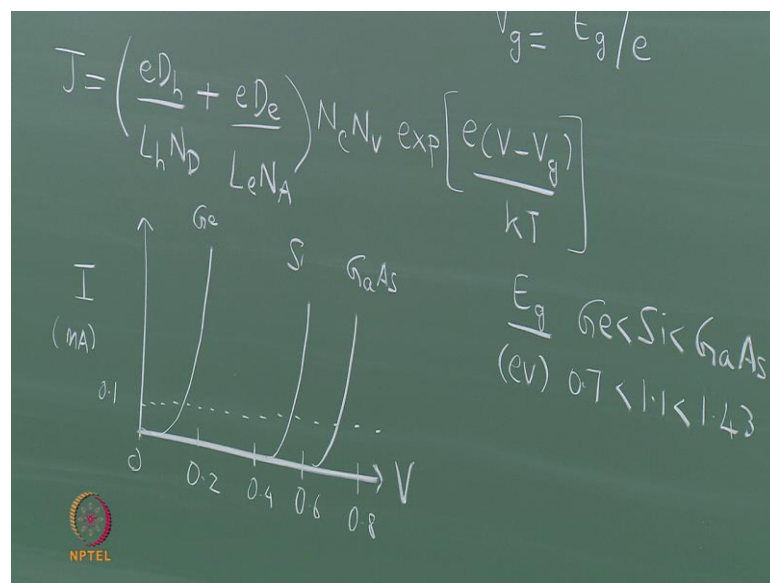
The image shows a chalkboard with three equations written in white chalk. The first equation is $J_{s0} = n_i^2 e \left(\frac{D_h}{L_h N_D} + \frac{D_e}{L_e N_A} \right)$ and $n_i^2 = N_c N_v \exp\left(-\frac{E_g}{kT}\right)$. The second equation is $J = J_{s0} \left\{ \exp\left[\frac{eV}{kT}\right] - 1 \right\}$ with the condition $\frac{eV}{kT} \gg 1$. The third equation is $J = \left(\frac{eD_h}{L_h N_D} + \frac{eD_e}{L_e N_A} \right) N_c N_v \exp\left[\frac{e(V - V_g)}{kT}\right]$ with the condition $V_g = E_g/e$. In the bottom left corner, there is a small NPTEL logo.

So, let me write this expression for J_{s0} one more time, J_{s0} is n_i square over e , D_h

over $L_h N_D$ plus D_e over $L_e N_A$. Now, n_i^2 which is the intrinsic carrier concentration is a material property, we now that n_i^2 is nothing but, $N_c N_v \exp(-E_g / kT)$ we can substitute for n_i^2 in this expression.

So, that J this is nothing but, $J_s \exp(eV / kT) - 1$. So, I am going to substitute J_s not n_i^2 and instead of n_i^2 and I will go to replace it $N_c N_v \exp(-E_g / kT)$; just for the sake of the argument in the find out E_g / kT is usually much wait to greater than 1. So, that I can going ignore this term minus 1 here. So, going to introduce another term v_g is nothing but, the band gap divided by e . So, if you do that J becomes equal to $e D_h / L_h N_D$ this is $E_d / L_e N_A N_c N_b \exp(eV - v_g / kT)$. So, v_g here is the external potential that he apply doing forward bias v_g is nothing but, band gap divided by e . So, plot current versus voltage for different semi conductors.

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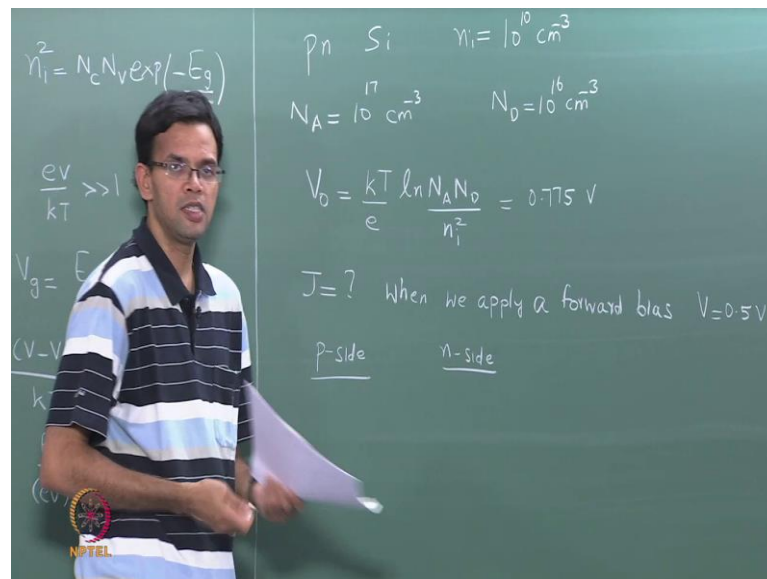


We find that if you want given a current the voltage will be higher, if the band gap is the higher. So, let me plot I versus v for 3 materials. So, he looks germanium, silicon an gallium arsenide. So, in terms of band gap E_g germanium smaller band gap, than silicon which smaller than gallium arsenide some typical values we now germanium is around 0.6 electron volts. This in eV silicon is this 1.1 germanium our sent is 1.43. So, may current will be in milli amps; so, voltage 0.

So, if find that, the curve for germanium comes first then you have, silicon final you

have gallium arsenide. So, germanium, silicon, gallium arsenide. So, that for given value of current. So, let say want current to be 0.1 milli amps the voltage is lowest for germanium, higher for silicon in even more higher for gallium arsenide. This is because you have v_g , which is band gap in that expression. So, let us now go ahead, look at example of a P-n junction in silicon and calculate some values, for the reverse saturation current in also the current though the P-n junction in forward bias.

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So, we are going to start with P-n junction at he that look at before we have N_A is 10 to the 17 and we have N_D is 10 to the 16, the material silicon. So, the intrinsic carrier concentration n_i 10 to the 10. So, we calculate contact potential in the P-n junction contact potential v not, we did this last class is nothing but, 0.675 volts. So, he want know what the current is. So, we want know value of J , when he apply to forward bias and let me take the value of the voltage to be 0.5 volts. So, let his write down the P-side an then n-side.

So, the first think we want to know, is how many carriers are injector because of the forward bias. So, from last class if you remembered, current in the case of P-n junction is due to the minority carriers. So, that we have electrons the inject in to the P-side; you have we have hole to the injected the in to the n-side that cost to the current.

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$J = ?$ When we apply a forward bias $V = 0.5 \text{ V}$

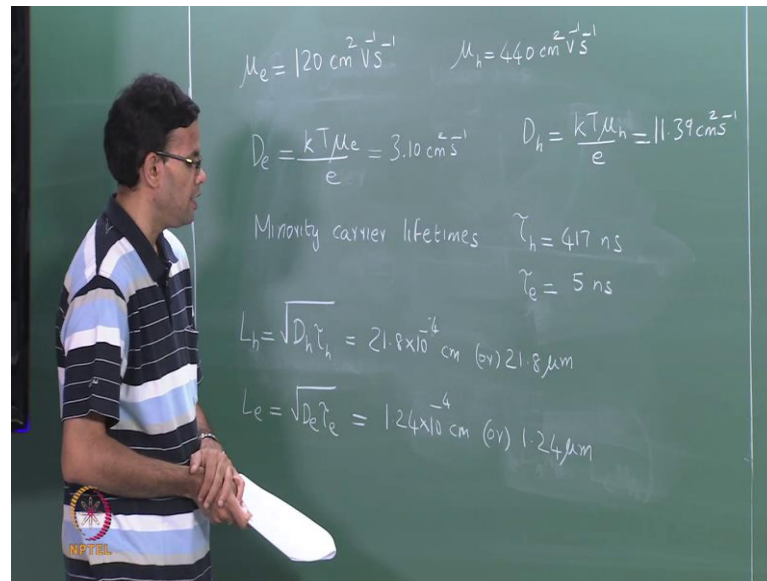
<u>P-side</u>	<u>n-side</u>	
$P_{p0} = N_A = 10^{17} \text{ cm}^{-3}$	$n_{n0} = N_D = 10^{16} \text{ cm}^{-3}$	$P_n(0) = P_{p0} \exp\left(\frac{-e(V_0 - V)}{kT}\right)$
$n_{p0} = 10^3 \text{ cm}^{-3}$	$P_{n0} = 10^4 \text{ cm}^{-3}$	↑ excess
		$P_n(0) = 2.4 \times 10^{12} \text{ cm}^{-3} \gg P_{n0}$
		$n_p(0) = n_{n0} \exp\left(\frac{-e(V_0 - V)}{kT}\right) = 2.4 \times 10^{11} \text{ cm}^{-3}$



If we write down the values; P_{p0} is nothing but, n_A is 10^{17} the concentration of electrons will be just n_i^2 over n_A that is 10^3 same way we can write for the n-side; the formula for the excess carriers. So, that $P_n(0)$ is nothing but, P_{p0} exponential minus $e(V_0 - V)$ over kT . So, V_0 here is the contact potential, V is the forward bias potential that is 0.5. So, $P_n(0)$ excess carriers. So, if you substitute the numbers and evaluate $P_n(0)$ turns out to be 2.4 times 10^{12} percent to meet square, percent to meet you q . So, this number is much greater than the equilibrium concentration of holes of the n side which is here. So, this is much greater, similarly we can calculate the excess electrons the P-side this is equal to 2.4.

So, this are the excess electrons on the excess holes, the injected due to the forward bias. Now this are still minority carriers ultimately they will be diffuse through material they recombine with majority carriers and get eliminated. So, in order to calculate the diffusion length, we need to know diffusion coefficient. So, let me first write down the mobility.

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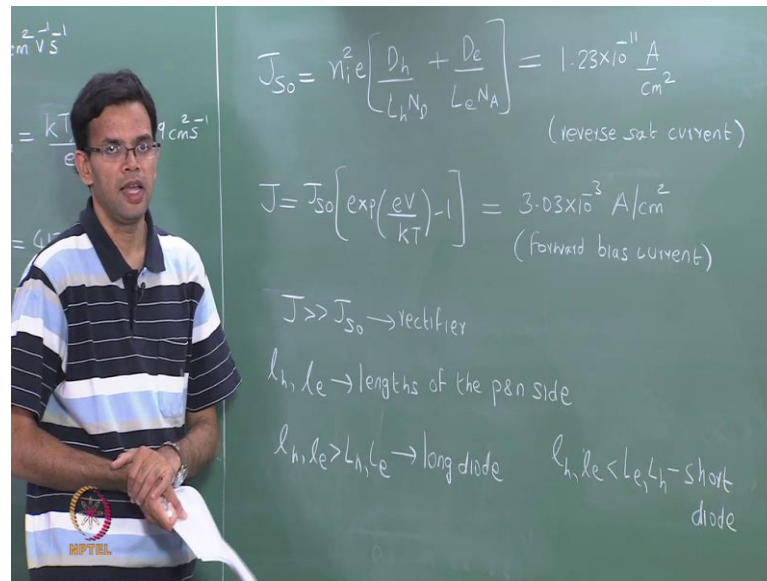


So, μ_e is the mobility of the electron and μ_h is the mobility of the holes. So, mobility in the case of the semiconductor usually goes down with increasing doping concentration. So, standard tables from which we can get the values of μ_e and μ_h as a function of the doping concentration. So, once we know μ we can calculate the diffusion coefficient; think by $kT\mu$ over e . So, substitute all the values this gives me diffusion coefficient of the electrons 3.1 centimeter square per second we can all. So, get the diffusion coefficient for the holes is 11.39 now, if you want to find diffusion length, we should also know how long this minority carriers can travel before they recombine. So, we need to know the carrier's lifetimes.

So, let me take the values τ_h is 417 nanoseconds and τ_e to be 5 nanoseconds. So, these are again values that we know typically this will also be defined upon the dopant concentration. So, τ_h is the lifetime of the holes traveling through the n side of the P-n junction and τ_e is for the electrons traveling for the P-side. So, we then calculated the diffusion length.

So, we can substitute the values we have D_h here in τ_h . So, this is 21.810 to the minus 4 centimeters or 21.8 micrometers. L_e is nothing but, $D_e \tau_e$ which is 1.24 as to 10 to the minus 4 centimeter or 1.24 micrometers. So, we have all the values that we need for calculating the reverse saturation current and the current during forward bias.

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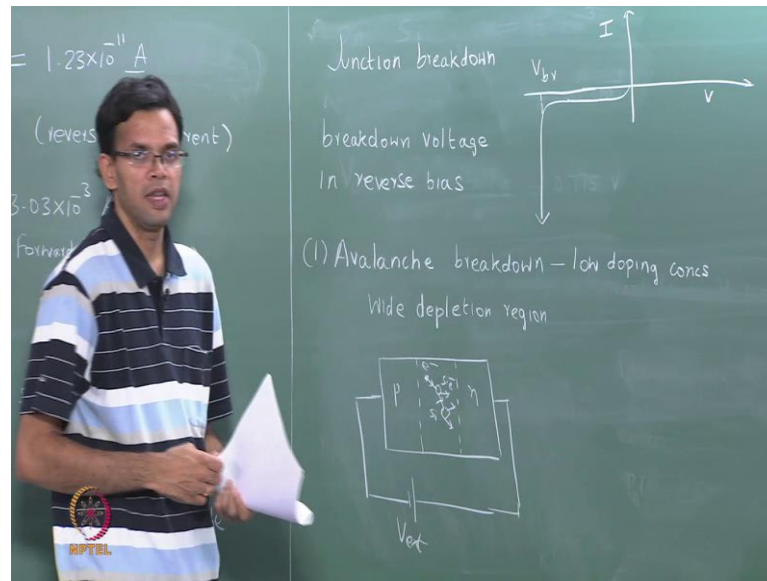


So, J_s not we can calculate; so, he have calculated all this values the diffusions coefficient diffusion length. So, we can substitute the numbers and evaluate J_s not. So, J_s not terms out 11 and pear percent 2 meter square. So, this is the reverse substitute current. So, this is the current well, he flowing trough if I have reverse bias the P-n junction. So, the current during forward bias nothing but, J_s not times exponential eV over kT minus 1 the voltages that we applied is 0.5 volt. So, J comes out b 3.03 and 10 to the minus 3 and pares percent to met to square. So, this is forward bias current.

So, earlier year we said that a P-n junction is a rectifier and we can see that, is because J is much greater than, J_s not; in this calculations we have assumed the length of the device, in larger than the diffusion length. So, let L_h and L_e the lengths. So, this refers to the physical lengths of Pn n-side. So, we have assumed the L_h and L_e are larger than the diffusion lengths. So, this kind of the diode called long diode.

So, the diffusion lengths are ward does in to this equation, if the psychical lengths is a actually shorter, if L_h and L_e are smaller than the diffusion lengths then, it is called short diode only difference in the calculation is the in the equation for the reverse saturation current intend of the difference lengths in the case of, short diode we will put the psychical lengths of the p and n side. So, let is again look at the I_v characteristic, let us look at the reverse bias side.

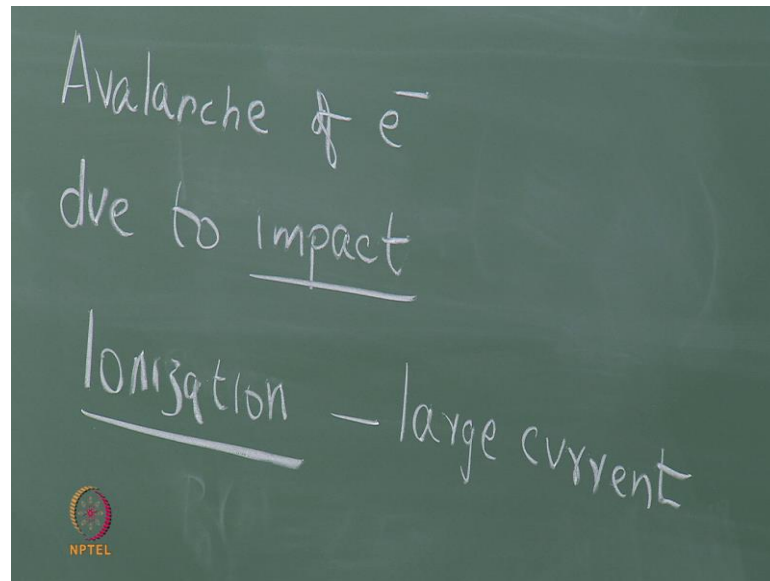
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We said that in the case of a P-n junction in reverse bias the current constant does not demand upon voltage. So, we side that the current is a constant, which is the equal to the reverse saturation current, but he turns out a at relay large voltage values the diode breaks down. So, that we have a large reverse current flowing to through the material. So, this voltage was this happens called your break down voltage this happens in reverse bias. So, when this happens we said the P-n junction has broken down and they are 2 mechanisms for this 1 is avalanche break down. So, this occurs for P-n junction with low doping. So, we have low doping concentrations on the P and the n-side. So, that we have wide depletion region.

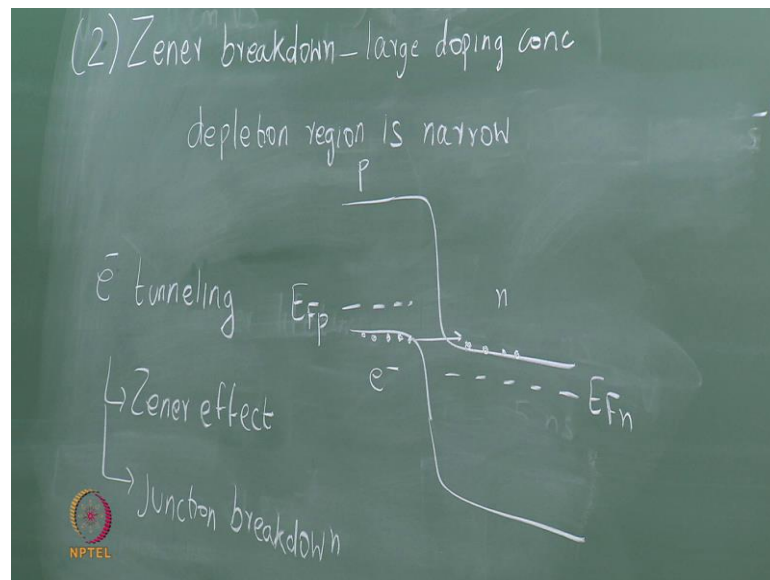
So, if we to draw this P-side that is my n-side this is under reverse bias. So, in this particular case an electron that is being accelerated by the fled we can essentially interact with silicon item and because it highest sufficient high enrage because of the large external potential that is applied that electron, can I niece silicon item an produce more electrons this in turn can interact with other in other silicon item. So, that you have an avalanche of electrons on productivity.

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So, this effect were the electrons it is a silicon item, an ionization it called impact ionization and the assets of this is have a large current. So, 1 mechanism of breakdown called the avalanche breakdown, a acres a low doping concentrations another mechanism of breakdown called the Zener breakdown.

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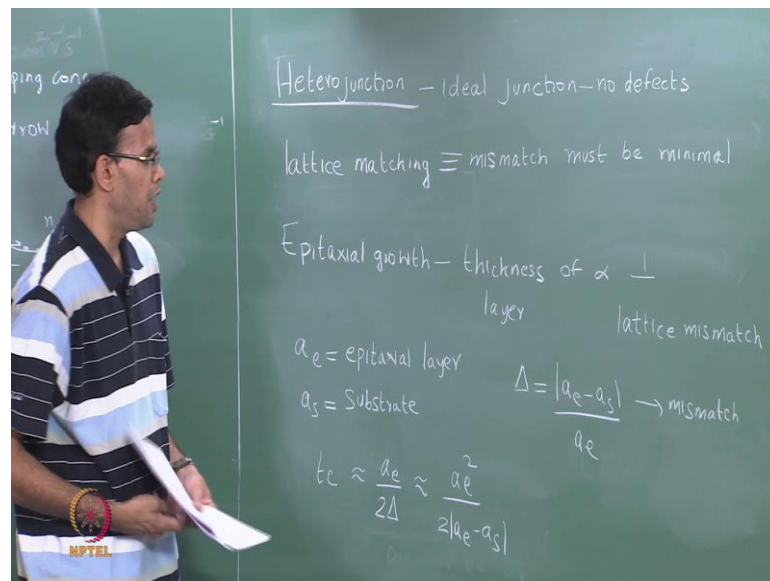


So, the Zener breakdown acres at large doping values; in this particular case, the depletion region our this narrow. So, if draw the enrage diagram for this, we just drag lightly. So, this is my P-side, that my n side these are the levels. So, we are in reverse

bias. So, there is a large barrier for because your definition with, is small we can have electrons tunneling from P to the n. So, this electron tunneling is called the Zener effect and because of that, you have a large current. So, we have to breakdown of the junction this leads to.

So, we have at a look P-n junction first in equilibrium and then in the case of bias, both forward and reverse, you also look at the 2 breakdown mechanism that are possible in reverse bias. So, for in the P-n junction we are considering, if considering material to be the same. So, we have the P and the n type, they are both the same material. So, they could be germanium or silicon or gallium arsenide, but the material is same. The next thing we are going to look at briefly is, what happens if you have 2 different materials. So, that you have hetero structure.

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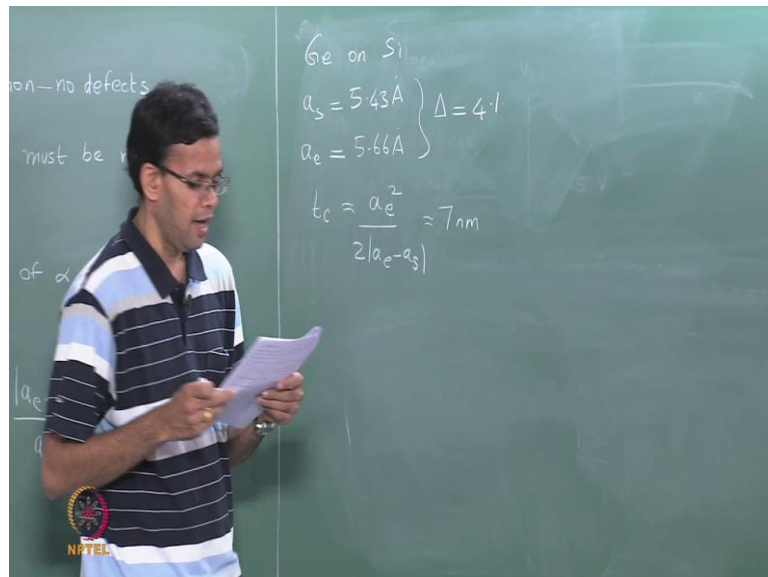


So, now we have hetero junction. So, that we have a junction formed, when P and n type of different materials. Once again when we have such hetero junction, they're going to assume that, we have ideal junction with no defects. So, this imposes restriction on the types of material set we can choose, in order to have an ideal junction with no defects, we must have the lattice matching between the 2 materials or if you want to put it in another way, the mismatch must be minimal. So, depending upon the degree of mismatch, we can control the thickness of the second layer on the first. So, if we look at, epitaxial growth the case of epitaxial growth, the layer you are trying to grow as same lattice constant

that of the substrate. So, that if there is lattice mismatch there is inherent strain in the material. So, the thickness of the layer you're trying to grow, is inversely proportional to the lattice mismatch.

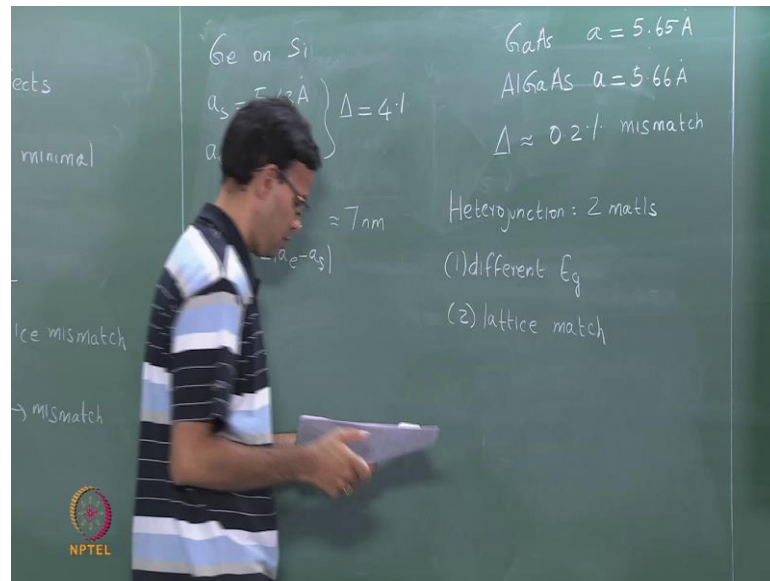
So, more the mismatch, the thinner the layer we can grow, ultimately if you mismatch large you are just going to have a large number of defects at the interface. So, a_e is the lattice constant of the epitaxial layer and the a_s is the lattice constant substrate then, we define mismatch $\Delta = \frac{a_e - a_s}{a_e}$ this is the mismatch. So, the thickness of the epitaxial layer that you can grow, t_c is proportional to a_e over Δ . So, this is the approximate expression. So, this is equal to $\frac{a_e^2}{2(a_e - a_s)}$. So, that is take an example, of silicon and germanium.

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So, let's say I am trying to grow a germanium layer on silicon; the lattice constant for silicon a_s is 5.43 for germanium. So, that is the lattice constant for the epitaxial layer is 5.66; in this particular case, the mismatch Δ if we try to put it in percentage is 4 percent. So, it is nothing but, $\frac{a_e - a_s}{a_e}$. So, the critical layer that we can grow, the thickness if you use the formula $\frac{a_e^2}{2(a_e - a_s)}$, this works out around 6 nanometers. It means; we can grow a layer of germanium on silicon of up to 6 nanometers they are free of inherent strain in germanium. If you go beyond that, you are going to form defects in the material.

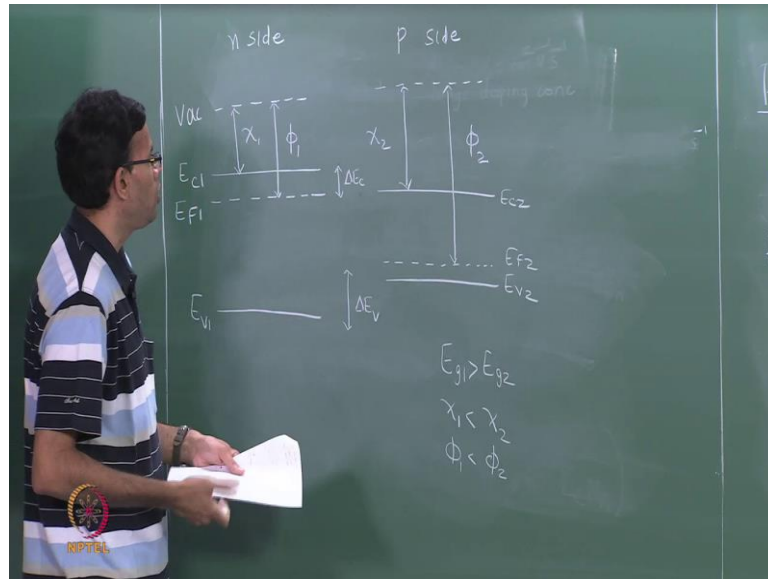
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The case of germanium on silicon, you actually have strain formation, in this kind of growth called as transmutation of growth intrusion of germanium on silicon. Let say, I have gallium arsenide growing on aluminum gallium arsenide or the other way, around this particular case, the lattice constants how much closer this is 3.65 this 3.66. So, here the lattice mismatch Δ is much smaller, typical around point 2 percent, silicon germanium it was 4 percent. So, the easier grow an epitaxial layers here.

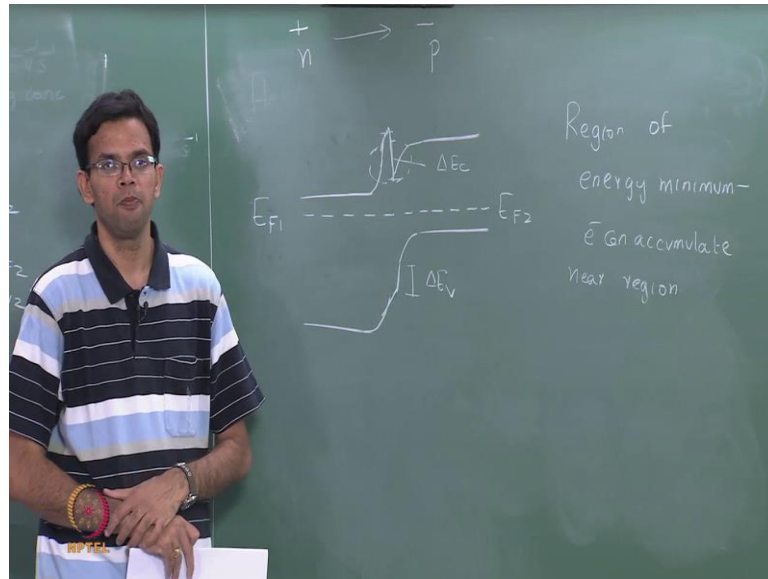
So, in the case of a heterojunction we want to choose two materials with different band gaps, we want different band gaps, because we want to exploit this difference to get interesting electronic properties, but at the same time we want a good lattice match. So, let us now look, at a band diagram in the case of a P-n heterojunction.

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So, I am going to consider junction; so, the first let me draw the n-side and I am doing to say, the they n-side has the higher band gap than the P-side. This is my n-side, this dotted line represents vacuum, this is the contention band D; that is, the valance band d and this is the fermi level. So, will just called this for the subscript 1. So, that this is material 1. So, we can define, an electron affinity is nothing but, the energy from the bottom of the contention band d to the vacuum level, we can also define my work function. This is doing to form a junction with a P type material, which as a smaller band gap this is the P-side. So, this is E_{c2} , E_{v2} , this is E_{f2} . And once again, we can write down values x_2 and the work function.

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So, now, I am forming P-n junction. So, I have $E_g 1$ greater than $E_g 2$; I have the electronic affinity going the other way, and the work functions also going in the other way. We can also define and the energy gap between the conduction bands of the 2 materials. So, that is ΔE_c we can also define energy gap, if in the valence ΔE_v . So, we went to put together this P-n junction. So, the first thing less at equilibrium the Fermi levels must line up. So, let me draw the P-n junction, the Fermi levels must line up. So, I have E_{F1} and E_{F2} . So, I have material 1, which is my n-side semiconductor this is the material with a wider band gap, than I have my P type material with a smaller band gap. So, if you look at this P-n junction you see that, the electrons go from the n to the P side.

So, that there is a net positive charge on the n-side there is net negative charge on the P-side. So, the electric field goes from n to P this is the same concept in a regular P-n junction and we know the bands bend up in the direction of the electric field. So, the bands have to bend up on the n-side and the bands on the P side bend down. So, we also said, there is a difference between the energy of the conduction bands. So, ΔE_c and the difference in the energy is of the valence band ΔE_v . So, when the bands bend they must make sense that different. So, that this gap is ΔE_v we just this and this gap ΔE_c .

So, now if I joined the is 2; we just we can get the P-n junction and the equilibrium. So, if he looks at this, this is different from how a Jn junction would look. If we have, the same material, specifically if he looks at the conduction band there is a region, were this energy minimum. So, that electrons in the P-side, we can essentially accumulate in a region near the junction that the region of energy minimum, which means electrons we can accumulate near that region, also the energy barriers are different for the conduction band d and valiance band . So, the barriers are different for the electron is in holes.

So, this can again affect the conductivity of the hetero junction. So, hetero junction have some important properties, when we look at optical properties because of the fact that we can have electron accumulation, if intrude of a P-n junction, were the n has a higher band gap, if you choose a P-n junction with P as a higher band gap. You see, accumulation holes near the junction. So, this we are done with p-n junction.

So, P-n junctions are a example, were we have an interface between 2 semi conductors they could be the P and the n of the same material or they could be the P and the n of the different material. In next class, we are going to look at devices, were we have you more than 1 junction for a example, of such devices is a transistor. So, the next class we are going to start looking at transient.